

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	Baer et al.)	Group No.:	1763
Serial No.:	10/675,697)	Examiner:	Arancibia
Filed:	09/30/2003)	Docket No.:	HSJ9-2003-0032US1

For: "METHOD OF FORMING A READ SENSOR USING PHOTORESIST

STRUCTURES WITHOUT UNDERCUTS WHICH ARE REMOVED USING CHEMICAL-MECHANICAL POLISHING (CMP) LIFT-OFF PROCESSES"

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

REQUEST FOR RECONSIDERATION

The Applicants respectfully submit this Request for Reconsideration for entry into the present application in response to the Office Action mailed on 05 April 2007.